	Application No.	Applicant(a)	
	Application No.	Applicant(s)	
Notice of Allowability	10/624,270	KIM ET AL.	
Notice of Allewability	Examiner	Art Unit	
	Thao P. Le	2818	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT F of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED i 5) or other appropriate comm RIGHTS. This application is	n this application. If not included unication will be mailed in due course. THIS	
1. \boxtimes This communication is responsive to <u>8/12/04</u> .			
2. The allowed claim(s) is/are 1-29 and 44.			
3. The drawings filed on 21 July 2003 are accepted by the E	Examiner.		
 4. ☐ Acknowledgment is made of a claim for foreign priority of a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have 2. ☐ Certified copies of the priority documents have 3. ☐ Copies of the certified copies of the priority documents have a linternational Bureau (PCT Rule 17.2(a)). * Certified copies not received: 	ve been received. ve been received in Applicati	on No	
Applicant has THREE MONTHS FROM THE "MAILING DATE noted below. Failure to timely comply will result in ABANDON! THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		e a reply complying with the requirements	
5. A SUBSTITUTE OATH OR DECLARATION must be subr INFORMAL PATENT APPLICATION (PTO-152) which give			
 CORRECTED DRAWINGS (as "replacement sheets") mu (a) including changes required by the Notice of Draftsper 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in 	rson's Patent Drawing Revie r's Amendment / Comment o	r in the Office action of he drawings in the front (not the back) of	
7. DEPOSIT OF and/or INFORMATION about the department attached Examiner's comment regarding REQUIREMENT	OSIT OF BIOLOGICAL MAT FOR THE DEPOSIT OF BI	ERIAL must be submitted. Note the DLOGICAL MATERIAL.	
 Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB. Paper No./Mail Date 6/1/04) 4. ☐ Examiner's Comment Regarding Requirement for Deposit) 6. ☐ Interview S Paper No /08), 7. ☑ Examiner's 8. ☑ Examiner's	oformal Patent Application (PTO-152) ummary (PTO-413), /Mail Date Amendment/Comment Statement of Reasons for Allowance	
of Biological Material	9. 🗌 Other		
		M	
	F	HOAI HO PRIMARY EXAMINER	

U.S. Patent and Trademark Office PTOL-37 (Rev. 1-04) **Examiner Amendment.**

An examiner's amendment to the record appears below. Should the changes

and/or additions be unacceptable to applicant, an amendment may be filed as provided

by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be

submitted no later than the payment of the issue fee.

Cancel Claims 30-43 due to non-elected claims, elected without traverse.

Information Disclosure Statement

The information disclosure statement (IDS) submitted on 6/1/04 was filed after

the mailing date of the applicantion. The submission is in compliance with the

provisions of 37 CFR 1.97. Accordingly, the information disclosure statement is being

considered by the examiner.

Claims 1-29 and 44 are pending.

Reason for allowance

Claims 1-29, 44 are allowed.

The following is an examiner's statement of reason for allowance:

None of the references of record teaches or suggests the claimed limitations

having a method of forming a semiconductor device which can form a self-aligned

contact hole by using an etch selectively between different material layers, the method

comprising, among other steps, the steps of patterning the trench masks and the gap fill insulating layer until a top surface of the active region is exposed to form a trench mask pattern and a gap fill insulating pattern, which define a slit-type opening extending across the active region, forming a gate pattern in the slit-type opening, removing the trench mask pattern to form a contact opening.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance".

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thao P. Le whose telephone number is 571-272-1785. The examiner can normally be reached on M-T (7-6).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Nelms can be reached on 571-272-1787. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Thao P. Le Examiner Art Unit 2818 David Nelms
Supervisory Patent Examiner
Technology Center 2800